AndrÃ¡s E VladÃ¡r

List of Publications by Year
in descending order

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15	564	10	15
papers	citations	h-index	g-index

933447 996975

15	15	15	587
all docs	docs citations	times ranked	citing authors

#	Article	IF	Citations
1	Metrology for the next generation of semiconductor devices. Nature Electronics, 2018, 1, 532-547.	26.0	249
2	Scanning electron microscope measurement of width and shape of 10 nm patterned lines using a JMONSEL-modeled library. Ultramicroscopy, 2015, 154, 15-28.	1.9	83
3	Scanning electron microscope dimensional metrology using a model-based library. Surface and Interface Analysis, 2005, 37, 951-958.	1.8	69
4	Helium ion microscopy and its application to nanotechnology and nanometrology. Scanning, 2008, 30, 457-462.	1.5	43
5	Real-Time Scanning Charged-Particle Microscope Image Composition with Correction of Drift. Microscopy and Microanalysis, 2011, 17, 302-308.	0.4	24
6	Contamination specification for dimensional metrology SEMs. Proceedings of SPIE, 2008, , .	0.8	19
7	New insights into subsurface imaging of carbon nanotubes in polymer composites via scanning electron microscopy. Nanotechnology, 2015, 26, 085703.	2.6	15
8	Three-Dimensional (3D) Nanometrology Based on Scanning Electron Microscope (SEM) Stereophotogrammetry. Microscopy and Microanalysis, 2017, 23, 967-977.	0.4	13
9	10nm three-dimensional CD-SEM metrology. Proceedings of SPIE, 2014, , .	0.8	12
10	A method to determine the number of nanoparticles in a cluster using conventional optical microscopes. Applied Physics Letters, 2015, 107, .	3.3	11
11	Optimizing hybrid metrology: rigorous implementation of Bayesian and combined regression. Journal of Micro/ Nanolithography, MEMS, and MOEMS, 2015, 14, 044001.	0.9	9
12	Virtual rough samples to test 3D nanometer-scale scanning electron microscopy stereo photogrammetry. Proceedings of SPIE, 2016, 9778, .	0.8	5
13	Contour metrology using critical dimension atomic force microscopy. Journal of Micro/ Nanolithography, MEMS, and MOEMS, 2016, 15, 044006.	0.9	4
14	Research Update: Electron beam-based metrology after CMOS. APL Materials, 2018, 6, .	5.1	4
15	Detecting nanoscale contamination in semiconductor fabrication using through-focus scanning optical microscopy. Journal of Vacuum Science and Technology B:Nanotechnology and Microelectronics, 2020, 38, 050602.	1.2	4